



566.38683CX1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: YOSHIDA, et al
Serial No.: 10/042,271
Filed: January 11, 2002
For: ABRASIVE METHOD OF POLISHING TARGET MEMBER AND
PROCESS FOR PRODUCING SEMICONDUCTOR DEVICE
Group (anticipated): 3723
Examiner (anticipated): D. Nguyen

SUPPLEMENTAL PRELIMINARY AMENDMENT

Assistant Commissioner of Patents
Washington, D.C. 20231

January 25, 2002

Sir:

Supplemental to the Preliminary Amendment filed on
January 11, 2002, please amend the application as follows:

IN THE CLAIMS

Please cancel Claims 1, 26 and 29.

Please add the following new Claims 30 - 49:

--30. An abrasive comprising cerium oxide particles, said
particles having a crystal grain boundary and having a maximum

RECEIVED

JUN 07 2004

TECHNOLOGY CENTER R3700